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다결정 산화구리의 반도성에 관한 연구

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A Study of the Semiconductivity of Polycrystalline Cuprous Oxide

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Abstract The semiconductivity of polycrystalline Cu_2O has been studied between 220°C and 680°C under partial pressures of oxygen from 4.06×10^{-3} to 10^{-5} mmHg. The plots of log conductivity vs 1/T at constant oxygen pressure were found to be linear, and the activation energies obtained from the slopes of these plots above the first transition point showed that the energies were greater under high oxygen pressure than under low pressure. The tsansition points between the stable range and the unstable range of Cu_2O were found from the curves. The dependence of the semiconductivity on the O_2 pressure, in the above temperature range, is shown hysterysis.

Introduction

Cuprous oxide has been studied by several researchers and there are a number of published reports. ^{1~6} Despite the difficulty of securing large single crystals⁶ of Cu₂O, these investigations involved the measurement of the conductivity of Cu₂O single crystals^{7~8} in the temperature range from 500 to 1100°C under oxygen pressures from 50 mmHg to 10⁻⁵ mmHg. This limited the research to the stable range of Cu₂O. The stability diagram shown in Fig. 1 was consulted to choose the range of temperatures and O₂ pressures.

In this research polycrystalline Cu₂O was used, with measurements carried out in the temperature range from 220°C to 680°C under oxygen

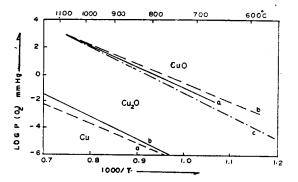


Fig. 1. Temperature dependence of the oxygen equilibrium pressure in the system Cu/Cu₂O/CuO; (a) Gundermann, Hauffe, and Wagner (b) quoted by Engelhard and (c) after Hauffe, as quoted by Böttger.

pressures from 4.06×10^{-3} to 10^{-5} mmHg, thus covering parts of both the stable and unstable ranges of Cu_2O near the transition points between

Cu2 Oand CuO. Semiconductors9~10 are generally classified as n-type whose current carriers are electrons and p-type whose carriers are positive holes. In general, the conductivity of a p-type semiconductor increases with increasing O2 pressure. The samples used in this study were pure polycrystalline Cu2O which is a p-type semiconductors due to the positive holes on the excess oxygen. However the conductivity of Cu₂O does not always increases with increasing O2 pressure because the Cu2O may be in the unstable range under some O2 pressures. In this case, one of the main factors affecting the conductivity is the phase transition of the Cu2O from the stable range to CuO in the Cu2O unstable range. The transition points and the activation energies obtained from the slopes of the plot of log conductivity vs 1/T are discussed in this paper.

Experiment

A. Sample preparation and electrical contacts. Specpure Cu rod refined by the Johnson-Matthey Co. was used for the sample preparation. Before annealing, the Cu rod was cut to a rectangular shape, polished with abrassive paper (No. 1000), and then etched in dil. HNO₃ solution. The Cu was preannealed at 800°C under air pressure for 350 hours. After the preannealing, the remaining Cu was removed and the Cu₂O reannealed at 800°C for 24 hours. Thus, the samples were pure polycrystalline Cu₂O. Pt leads were connected to the sample

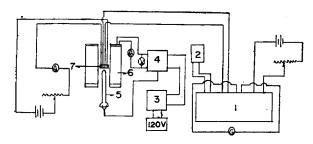
Table 1. Conductivity (or σ) at various temperatures. (1.2×10⁻² mmHg oxygen pressure)

Temp.	10000/T	Amp.	Volt	σ(ohm-1 Cm-1)	
260	1.8762	3. 00 × 10 ⁻⁵	0. 32483	4. 61781 × 10 ⁻⁴	
280	1.8083	6. 00×10 ⁻⁵	0. 39800	7. 53769×10^{-4}	
300	1.7452	9.00×10 ⁻⁵	0. 49237	9. 13947×10^{-4}	
320	1. 6863	1. 15×10^{-5}	0. 52800	1. 08902×10^{-3}	
340	1. 6313	1.60×10^{-4}	0. 52284	1. 53010×10^{-3}	
360	1.5798	2.00×10^{-4}	0. 53376	1.87350×10^{-3}	
380	1.5314	2.45×10^{-4}	0.52672	2. 32571×10^{-3}	
400	1. 4859	3.00×10^{-4}	0.51292	2.92443×10 ⁻³	
420	1. 4430	4.00×10 ⁻⁴	0.45100	4. 43459×10^{-3}	
440	1.4025	4.70×10 ⁻⁴	0.42280	5. 55818×10^{-3}	
460	1.3643	5.50×10^{-4}	0. 39852	6. 90053×10 ⁻³	
480	1. 3280	7. 00×10 ⁻⁴	0. 35216	9.93866×10^{-3}	
500	1. 2937	8.40×10 ⁻⁴	0. 32602	1. 28826×10^{-2}	
520	1. 2610	1.15×10^{-3}	0. 31765	1.81017×10^{-2}	
540	1.2300	1.05×10^{-3}	0. 17480	3.00343×10^{-2}	
560	1. 2005	1. 05×10^{-3}	0. 16335	3. 21396×10^{-2}	
580	1. 1723	1. 05×10^{-3}	0. 12320	4. 26137×10^{-2}	
600	1. 1455	1.06×10 ⁻¹	0.08530	6.21335×10^{-2}	
620	L 1198	9.50×10^{-4}	0.05242	8.89180×10^{-2}	
640	1.0953	1. 00×10^{-3}	0. 04405	1.13507×10^{-1}	
660	1. 0718	1.00×10^{-3}	0. 02253	1.53563×10 ⁻¹	
680	1. 0493	1.00×10^{-3}	0.02320	2.15517×10^{-1}	

after it was polished, etched, washed and dried. The four leads winding method¹¹⁻¹³ was used in this measurement. The sample size and the distances between the leads were determined by reading microscope.

B. Furnance assembly and vacuum system.

The schematic drawing of the furnace assembly and vacuum system was reported in the earlier paper. (14) The vycore sample container was connected to the vacuum system by a glass joint to provide easy access to the sample and contacts. This connection also contained a stopcock



Schematic drawing of the measurement circuit.
 Leeds and Northrup K-2 potentiometer 2.
 Standard cell 3. Powerstat 4. Temp. controller 5. Thermocouple 6. Electrical Furnace
 Sample

so that the desired pressure could be maintained. Temperature control of the sample was possible by moving the furnace up or down with a jack. The temperature at the sample position was determined from a calibration curve between the sample position temperature and the temperature shown on temperature controller data for which was initially obtained using a Pt-Rh thermocouple. The low oxyen pressure down to 10^{-5} mmHg was obtained with a Cenco Hyvac fore pump and CEC GF-20A oil diffusion pump.

C. Measurement circuit As shown in Fig. 2 the two inner leads from the sample were connected to a Leeds and Northrup K-2 Potentiometer to measure the voltage and the outer two leads to an ammeter to check the D. C. current. The sensitivity of the galvanometer

was 0.005 μa/mm.

D. Experimental procedure Under controlled conditions of temperature and pressure, the sample was annealed for 2 hours. Then, as the temperature was gradually raised or lowered, current-voltage measurements were made at intervals of 20°C; with these data, the conductivity of the sample was calculated using the known distances between contacts and the cross sectional area of the sample. Measurements were made on a total of 5 samples, and a typical set of results at constant oxygen pressure of 1.2×10^{-2} mmHg is shown in Table 1. The results of measurements for a given condition were similar for all samples.

Results and discussion

Readings on the samples were taken over a complete cycle of the temperature range for a given O₂ pressure starting from the high tem-

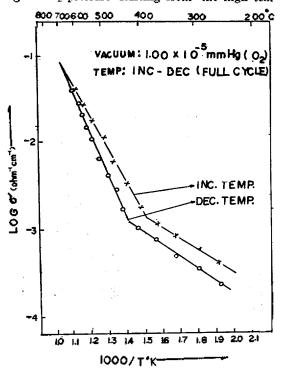


Fig. 3. LOG ovs 1/T

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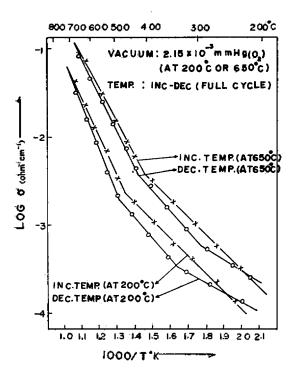


Fig. 4. Log o vs 1/T

perature and, proceeding toward the low end, and then back to the high temperature. shown in Fig. 3, the conductivity with increasing temperature was higher than those with decreasing temperature for a given temperature. This tendency is obvious in the lower temperature region, and negligible above 650°C. This could be explained on the basis that temperature or oxygen pressure equilibrium of the sample was established more easily in the higher temperature regions. There is some additional concern over the validity of the curves at O2 pressures lower than 10⁻⁴ mmHg due to the Knudsen effect. Since the sample is at a high temperature while the ionization gauge reading the pressure is at room temperature, a correction for the O2 pressure should be made for each experimental point. However, the points shown were plotted without applying the Knudsen correction since it was felt that the variation in the conductivity due to the changing temperature

far outweighed any change due to the changing O₂ pressure caused by the changing temperature. Measurements made with an oxygen pressure of 2. 15×10⁻⁸ mmHg and sample temperature of 200°C and 650°C respectively are shown in Fig. 4. From these data it can be concluded that with conversion to the same temperature the former would be at a higher oxygen pressure. From a theoretical view, the conductivity of p-type semiconductors such as Cu₂O should be larger at higher oxygen pressures, but in this temperature range, the data does not obey the theory. It can be seen that Knudsen effect are negligible and one of the main factor affecting the conductuctivity of the Cu2O is not the oxygen pressure but whether the sample is in the stable range or not. In the case of Fig. 5, the conductivity change due to oxygen pressures does not follow Wagner and Hammen's theory (15). Wagner and Hammen were the first to

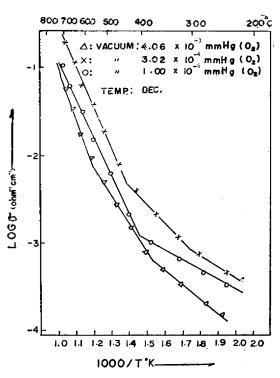


Fig. 5. Log σ vs 1/T

postulate an equilbrium between the O_2 and solid Cu_2O of the form

$$Cu_2O + O_2 \Longrightarrow Cu_2O + 4V_{\delta_n} + 4P$$

where V_{C_N} represents a Cu ion vacancy and p represents a positive hole. They obtained the relation $P^8 = k_{0x}P(O_2)$. They then assumed that the conductivity was due primarily to hole conduction and arrived at the relation

$$\sigma = k_{\theta x} (P(O_2))^{1/8}$$

However, the experimental work by Wagner and coworker¹⁶ showed that σ varied with $P(O_2)$ to the 1/7 power. Our data obtained on the polycrystalline Cu_2O under the special condition does not support the work of Wagner. It shows that the conductivity changes depend

largely on the condition in which the sample is in the stable range or not rather than O2 pressure. At 10⁻⁵ mmHg O₂ pressure only one transition point appears in the log conductivity vs 1/T plot, while at pressures above 10⁻⁴ mmHg, two points appear. Comparison of the Cu₂O stable range diagram with the above results shows that at oxygen pressures above 10⁻⁴ mmHg a Cu₂O-CuO equilibrium is established between the two transition points but that at oxygen pressures below 10⁻⁴ mmHg only the transition from Cu₂O to CuO due to oxygen deficiency appears. The transition points are lined up with the phase diagram (Fig. 1) and therefore, we can extended the stability curve with conductivity data below 600°C.

The activation energies, calculated from the

Condition	O, pressure	E _{act} .1	T. P. — I	E _{act} .2	T. P. — II	Eact, 3
Increasing Temperature	4. 06×10 ⁻³	25. 17Kcal/mole (1. 09ev)	553. 45° C	10. 40Kcal/mole (0. 45ev)	613.50° C	8. 32Kcal/mole (0. 36ev)
	1. 21×10 ⁻³	24.23 " (1.05")	546.67° C	16.02 " (0.70")	389. 25° C	8. 08 " (0. 35")
	1.00×10 ⁻⁶	14.67 " (0.64")	402. 68° C	5.95 " (0.26")		_
Decreasing Temperature	4.06×10 ⁻⁴	22.31 " (0.97")	550. 05° C	14.68 " (0.64")	372. 16° C	7.32 " (0.31 ")
	3. 02×10 ⁻⁴	21.05 " (0.91")	446. 42° C	10.04 " (0.44")	305. 03° C	6.20 " (0.22")
	1.00×10 ⁻⁶	19.83 " (0.86")	411.93° C	5.16 " (0.22 ")	_	

Table 2. activation energy at various conditions

slopes of the log conductivity vs 1/T curves are listed in Table 2. The activation^{17~18} energy is the summation of the vacancy formation energy and the counter-migration energy of the electron. The activation energies increase with increasing oxygen pressures at temperatures above the first transition point, though in other temperature ranges there are some irregularities. As the sensitivity of the Galvanometer used was not adequate for measurements below 220°C,

it was impossible to check the conductivity at low temperatures.

Acknowledgment.

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